

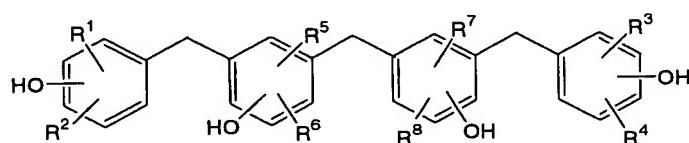
WHAT IS CLAIMED IS:

1. A positive photoresist composition comprising:

(A) an alkali-soluble resin;

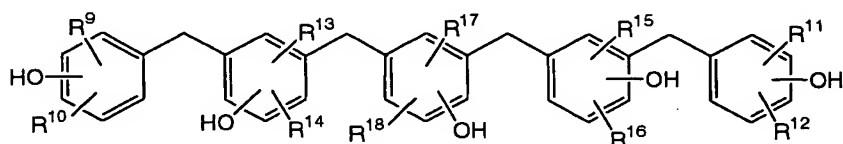
(B) a photosensitizer comprising a quinonediazide ester between a naphthoquinonediazidosulfonic acid compound and at least one of a compound represented by following Formula

(I):



(I)

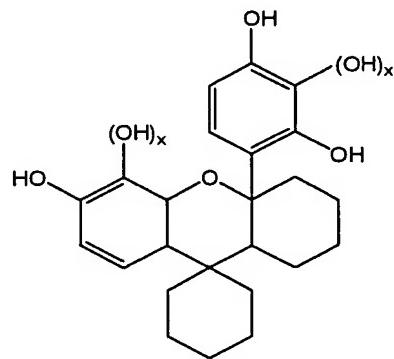
wherein R<sup>1</sup>, R<sup>2</sup>, R<sup>3</sup>, R<sup>4</sup>, R<sup>5</sup>, R<sup>6</sup>, R<sup>7</sup> and R<sup>8</sup> are each independently a hydrogen atom or an alkyl group having from 1 to 3 carbon atoms, and a compound represented by following Formula (II):



(II)

wherein R<sup>9</sup>, R<sup>10</sup>, R<sup>11</sup>, R<sup>12</sup>, R<sup>13</sup>, R<sup>14</sup>, R<sup>15</sup>, R<sup>16</sup>, R<sup>17</sup> and R<sup>18</sup> are each independently a hydrogen atom, an alkyl group having from 1 to 3 carbon atoms or a cyclohexyl group; and

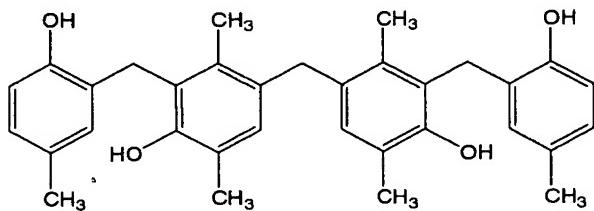
(C) a sensitizer comprising at least one of compounds represented by following Formula (III):



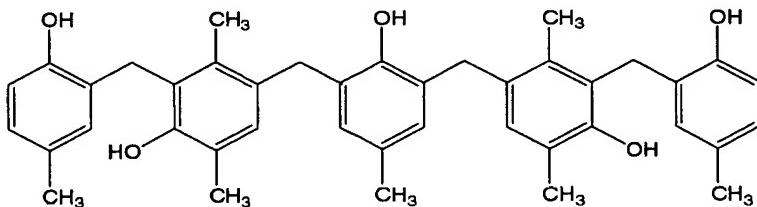
(III)

wherein x is 0 or 1.

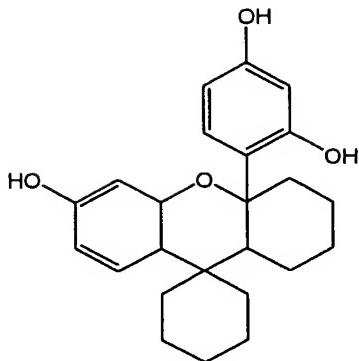
2. The positive photoresist composition according to claim 1, wherein the compound represented by Formula (I) is a compound represented by the following formula:



3. The positive photoresist composition according to claim 1, wherein the compound represented by Formula (II) is a compound represented by the following formula:



4. The positive photoresist composition according to claim 1, wherein the compound represented by Formula (III) is a compound represented by the following formula:



5. The positive photoresist composition according to claim 1, wherein the compound represented by Formula (III) is a compound represented by the following formula:

